

## **AMENDMENTS TO THE CLAIMS**

The following listing of claims will replace all prior versions and listings of claims in the application.

### **LISTING OF CLAIMS**

1. – 2. (Cancelled).

3. (Currently Amended) A mask vapor deposition system comprising:  
an electrostatic chucking mechanism for attracting a subject for deposition using  
electrostatic attraction;

an deposition mask, brought into close contact with a face of the deposition  
subject, for depositing a deposition material in a predetermined pattern, the face being  
reverse to that of the deposition subject attracted by the electrostatic chucking  
mechanism, the mask being made of silicon;

an evaporation source for evaporating the deposition material; and  
a vacuum chamber,  
wherein the mechanism, mask, and source are at least placed in the vacuum  
chamber.

4. (Cancelled).

5. (Currently Amended) A mask vapor deposition system comprising:  
a deposition mask for attracting a subject for deposition using electrostatic  
attraction and depositing a deposition material on the deposition subject in a  
predetermined pattern, the mask being made of silicon and having positive and negative  
electrodes thereon;

an evaporation source for evaporating the deposition material; and

a vacuum chamber,  
wherein the mask and source are at least placed in the vacuum chamber.

6. – 12. (Cancelled).

13. (Currently Amended) An apparatus for manufacturing a display panel,  
comprising:

an electrostatic chucking mechanism for attracting a glass substrate that is a  
subject for deposition using electrostatic attraction;  
a deposition mask to be brought into close contact with a face of the glass  
substrate in order to deposit an organic material, which is used for forming  
electroluminescent elements on the glass substrate in a predetermined pattern, the face  
being reverse to that of the glass substrate attracted by the electrostatic chucking  
mechanism, the mask being made of silicon;

an evaporation source for evaporating the organic material; and  
a vacuum chamber,  
wherein the mechanism, mask, and source are at least placed in the vacuum  
chamber.

14. – 15. (Cancelled).